

L Number	Hits	Search Text	DB	Time stamp
1	1021	438/424.ccls.	USPAT	2004/10/20 19:11
2	347	438/427.ccls.	USPAT	2004/10/20 19:11
3	169	438/453.ccls.	USPAT	2004/10/20 19:11
4	757	438/618.ccls.	USPAT	2004/10/20 19:12
5	1102	438/622.ccls.	USPAT	2004/10/20 19:12
6	279	438/636.ccls.	USPAT	2004/10/20 19:12
7	1576	438/637.ccls.	USPAT	2004/10/20 19:12
8	132	438/444.ccls.	USPAT	2004/10/20 19:12
9	723	438/700.ccls.	USPAT	2004/10/20 19:12
10	770	438/710.ccls.	USPAT	2004/10/20 19:12
11	610	438/725.ccls.	USPAT	2004/10/20 19:13
12	189	deloach-juanita\$.in. smith-brian\$.in.	USPAT	2004/10/20 19:14
13	76	deloach-juanita\$.in. smith-brian\$.in.	US-PPGPUB	2004/10/20 19:13
14	143	deloach-juanita\$.in. smith-brian\$.in.	EPO; JPO; DERWENT; IBM_TDB	2004/10/20 19:13
15	90263	(trench open\$6 groov\$6 recess\$6) and plasma	USPAT	2004/10/20 19:19
16	28121	((trench open\$6 groov\$6 recess\$6) and plasma) and (resist photoresist)	USPAT	2004/10/20 19:16
17	13154	((trench open\$6 groov\$6 recess\$6) and plasma) and (resist photoresist)) and ((resist photoresist) same plasma)	USPAT	2004/10/20 19:17
18	892	((trench open\$6 groov\$6 recess\$6) and plasma) and (resist photoresist)) and ((resist photoresist) same plasma)) and ((resist photoresist) adj2 plasma)	USPAT	2004/10/20 19:20
19	711	((trench open\$6 groov\$6 recess\$6) and plasma) and (resist photoresist)) and ((resist photoresist) same plasma)) and ((resist photoresist) adj2 plasma)) and (isolat\$9 transistor interconnect\$6)	USPAT	2004/10/20 19:21
21	13573	(trench open\$6 groov\$6 recess\$6) and plasma and (resist photoresist)	US-PPGPUB	2004/10/20 19:20
23	294	((trench open\$6 groov\$6 recess\$6) and plasma and (resist photoresist)) and ((resist photoresist) adj2 plasma)	US-PPGPUB	2004/10/20 19:20

24	2160	(trench open\$6 groov\$6 recess\$6) and plasma and (resist photoresist)	EPO; JPO; DERWENT; IBM_TDB	2004/10/20 19:20
25	84	((trench open\$6 groov\$6 recess\$6) and plasma and (resist photoresist)) and ((resist photoresist) adj2 plasma)	EPO; JPO; DERWENT; IBM_TDB	2004/10/20 19:20
26	70	((((trench open\$6 groov\$6 recess\$6) and plasma and (resist photoresist)) and ((resist photoresist) adj2 plasma)) and ((trench open\$6 groov\$6 recess\$6) same plasma)	EPO; JPO; DERWENT; IBM_TDB	2004/10/20 19:21
27	1793	((trench open\$6 groov\$6 recess\$6) and plasma and (resist photoresist)) and ((trench open\$6 groov\$6 recess\$6) same plasma)	EPO; JPO; DERWENT; IBM_TDB	2004/10/20 19:21
28	442	(((trench open\$6 groov\$6 recess\$6) and plasma and (resist photoresist)) and ((trench open\$6 groov\$6 recess\$6) same plasma)) and (isolat\$9 transistor interconnect\$6)	EPO; JPO; DERWENT; IBM_TDB	2004/10/20 19:21